

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
29 December 2005 (29.12.2005)

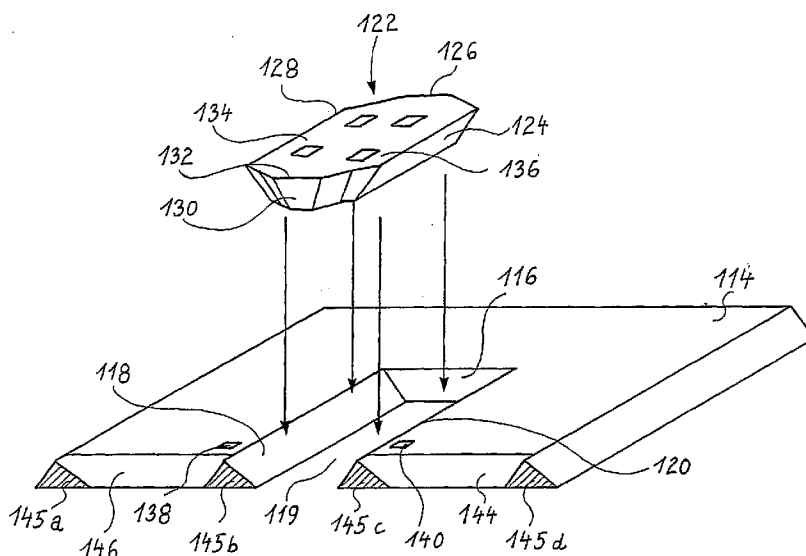
PCT

(10) International Publication Number
WO 2005/124371 A1

- (51) International Patent Classification⁷: **G01R 3/00**
- (21) International Application Number:
PCT/DK2005/000417
- (22) International Filing Date: 21 June 2005 (21.06.2005)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
EP 04388039.2 21 June 2004 (21.06.2004) EP
EP 04388065.7 28 September 2004 (28.09.2004) EP
EP 05388003.5 27 January 2005 (27.01.2005) EP
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- (81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).
- Published:
— with international search report

[Continued on next page]

(54) Title: A METHOD FOR PROVIDING ALIGNMENT OF A PROBE



(57) Abstract: A method for providing alignment of a probe relative to a supporting substrate, comprises the steps of providing the supporting substrate defining a planar surface and an edge, the substrate further defining a first crystal plane, providing a first mask at the surface of the supporting substrate, the first mask defining a first exposed area on the surface at the edge, and providing a specific etch reagent, a recess formed by the etch reagent etching the first exposed area, the recess defining a first sidewall an opposing second sidewall, an end wall remote from the edge, and a bottom wall. The method further comprises providing a probe substrate defining a planar surface and a second crystal plane identical to the first crystal plane and positioning the probe substrate so that the first and the second crystal planes are positioned identically when forming the probe from the probe substrate using the specific etch reagent, the probe defines congruent surfaces to the first sidewall and the second sidewall.

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